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(12) **United States Design Patent**
Wu

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- (54) **MASK**
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- (72) Inventor: **Chun-Hung Wu**, New Taipei (TW)
- (**) Term: **15 Years**
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- (51) **LOC (11) Cl.** **21-03**
- (52) **U.S. Cl.**
USPC **D21/660**
- (58) **Field of Classification Search**
USPC D21/576-579, 585, 588, 593, 594, 612,
D21/621, 623, 625, 626, 627, 631, 633,
D21/635, 639, 645, 649, 658, 659-661
CPC A42B 3/20; A42B 3/225; A41D 13/11;
A41D 13/1107
See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

452,155	A *	5/1891	Ahlstrom	A41D 13/11 2/206
587,687	A *	8/1897	Harder	A41D 13/11 2/206
885,802	A *	4/1908	Sterrick	A41D 13/11 2/206
D172,060	S *	4/1954	Reich	D11/136
D307,954	S *	5/1990	Alber	D21/660
D335,937	S *	5/1993	Owens	D21/660
D355,393	S *	2/1995	Bezener	D11/133
D434,852	S *	12/2000	Kim	D24/200
D444,920	S *	7/2001	Hicks, Jr.	D29/111
D449,902	S *	10/2001	Pernicka	D29/111
D485,874	S *	1/2004	Reitz	D21/660
D496,698	S *	9/2004	Reesman	D21/660

6,938,272 B1 * 9/2005 Brown A42B 3/20
2/424
D634,373 S * 3/2011 Marrero D21/659
D665,536 S * 8/2012 Jenke D29/108
(Continued)

OTHER PUBLICATIONS

<http://www.theatregarage.ca/event/nnask-making-nnegan-koshka/>—
Retrieved Jun. 5, 2018.*

(Continued)

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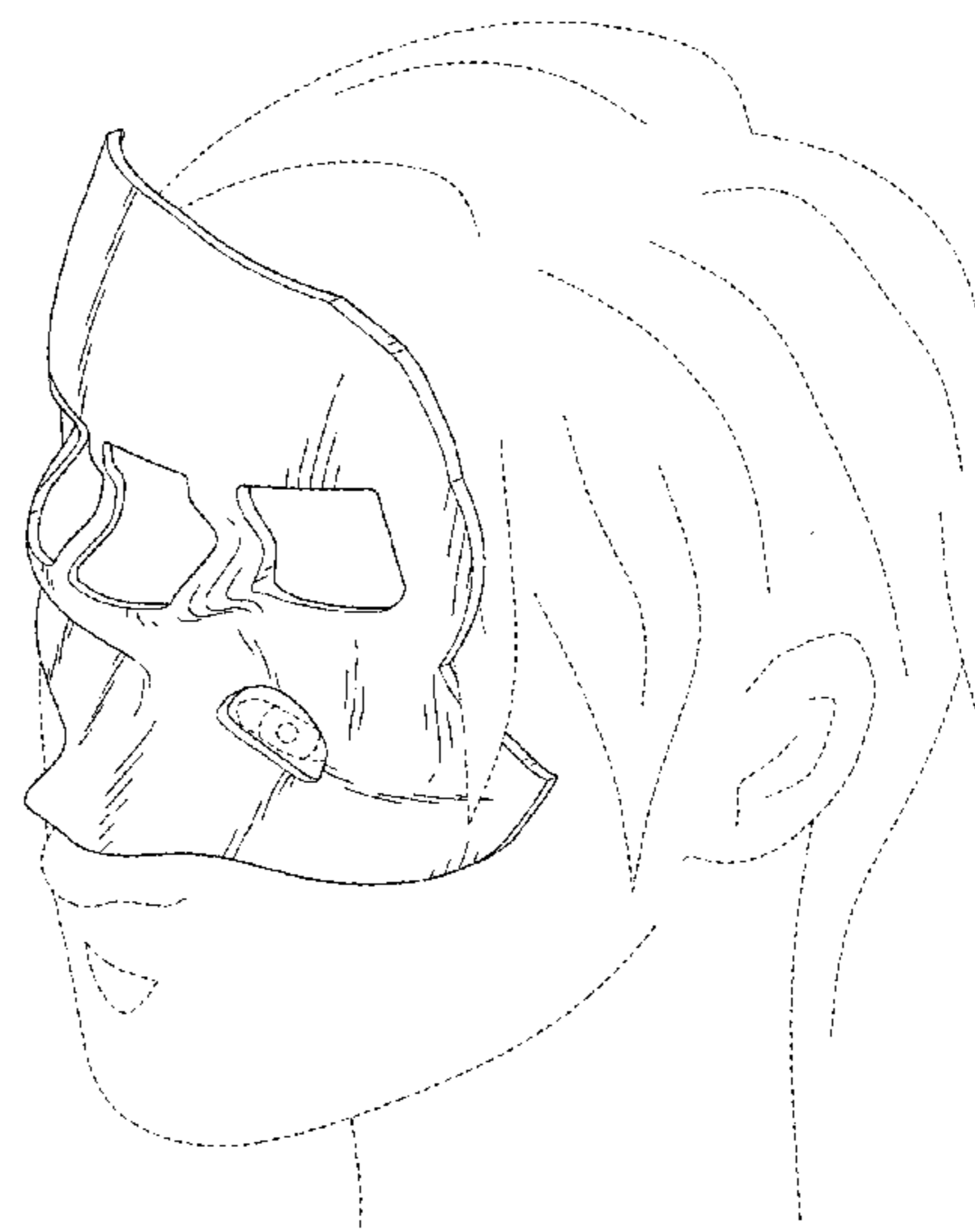
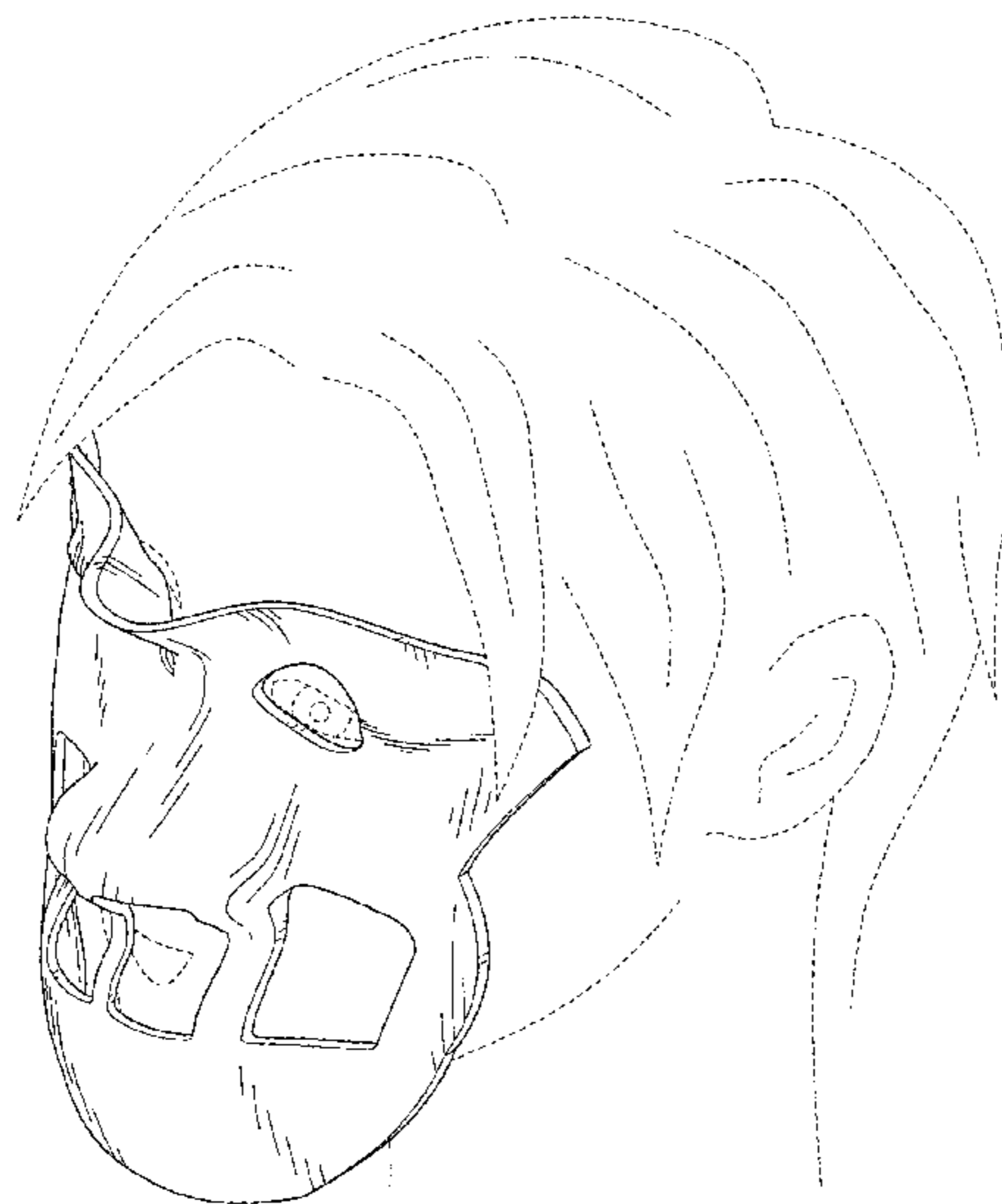
(57) **CLAIM**

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a mask, showing my new design;
FIG. 2 is a front elevational view thereof in which the profile lines 8-8 and 9-9 herein form no part of the claimed design;
FIG. 3 is a rear elevational view thereof;
FIG. 4 is a left elevational view thereof;
FIG. 5 is a right elevational view thereof;
FIG. 6 is a top plan view thereof;
FIG. 7 is a bottom plan view thereof;
FIG. 8 is a cross-sectional view along line 8-8 shown in FIG. 3;
FIG. 9 is a cross-sectional view along line 9-9 shown in FIG. 3;
FIG. 10 is the mask in condition of use, where it is adapted to fit a lower portion of a human's face; and,
FIG. 11 is the mask in condition of use, where it is adapted to fit an upper portion of the human's face.
The broken line within figure drawings represents unclaimed environment only, and forms no part of the claimed design.

1 Claim, 9 Drawing Sheets



(56)

References Cited

U.S. PATENT DOCUMENTS

D668,022 S * 10/2012 Mergler D2/741
D715,454 S * 10/2014 Riggons D24/206
D768,927 S * 10/2016 Eisenberg D28/9
D802,670 S * 11/2017 Wu D20/23
D818,200 S * 5/2018 Broaddus D29/110

OTHER PUBLICATIONS

<https://www.bleedingcool.com/2017/09/23/casey-jones-neca-mask/>—
Published Sep. 23, 2017.*

* cited by examiner

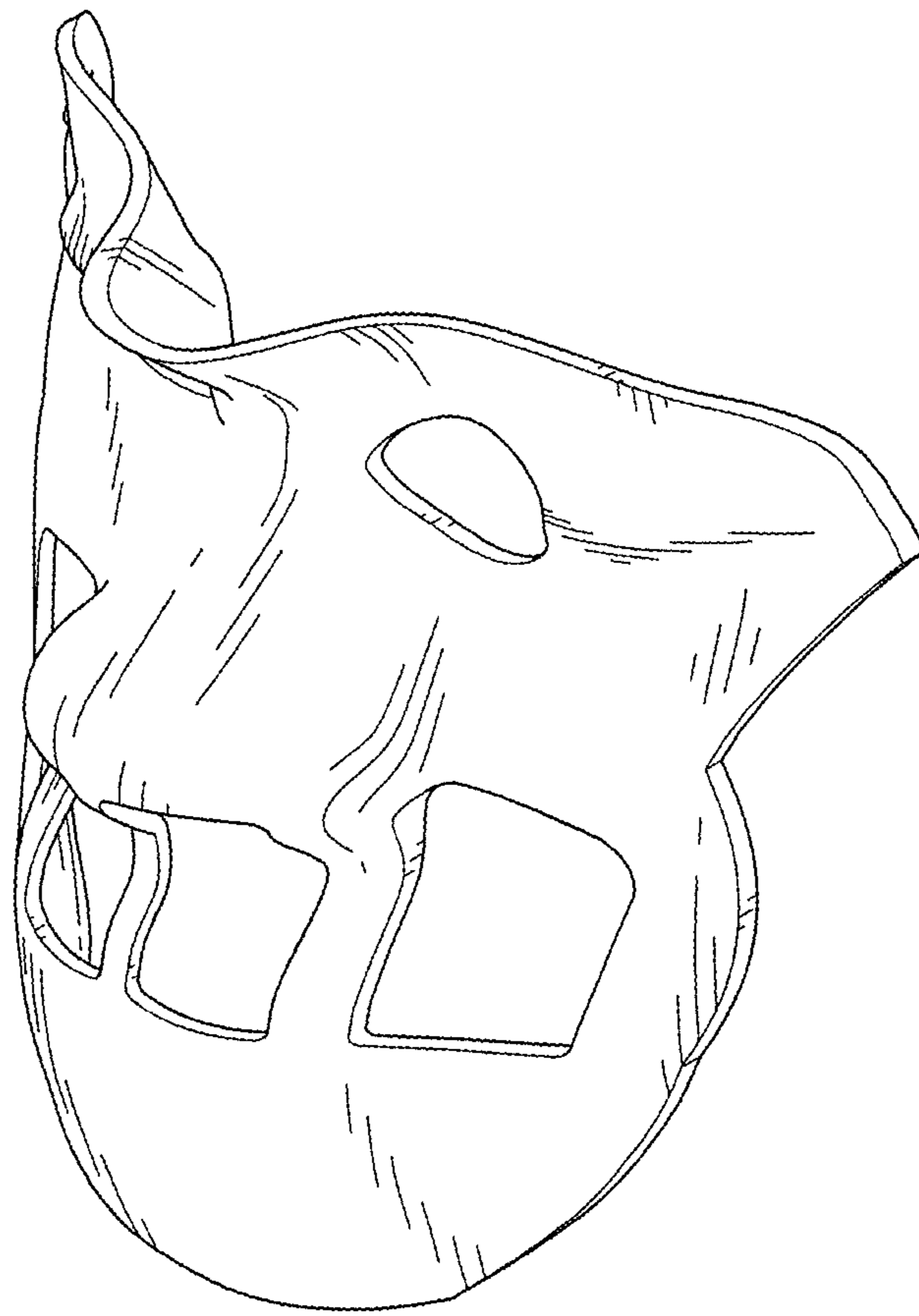


FIG.1

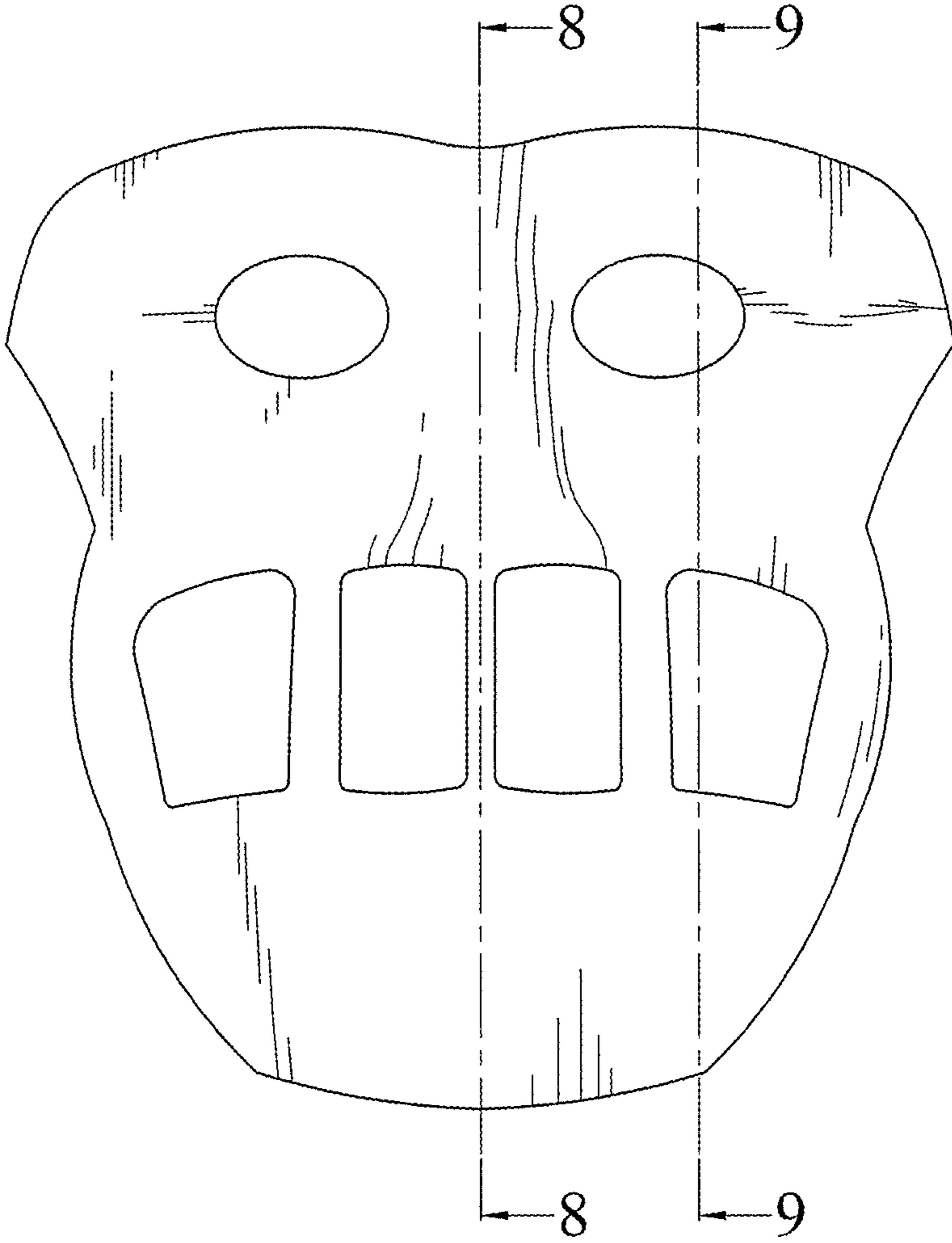


FIG.2

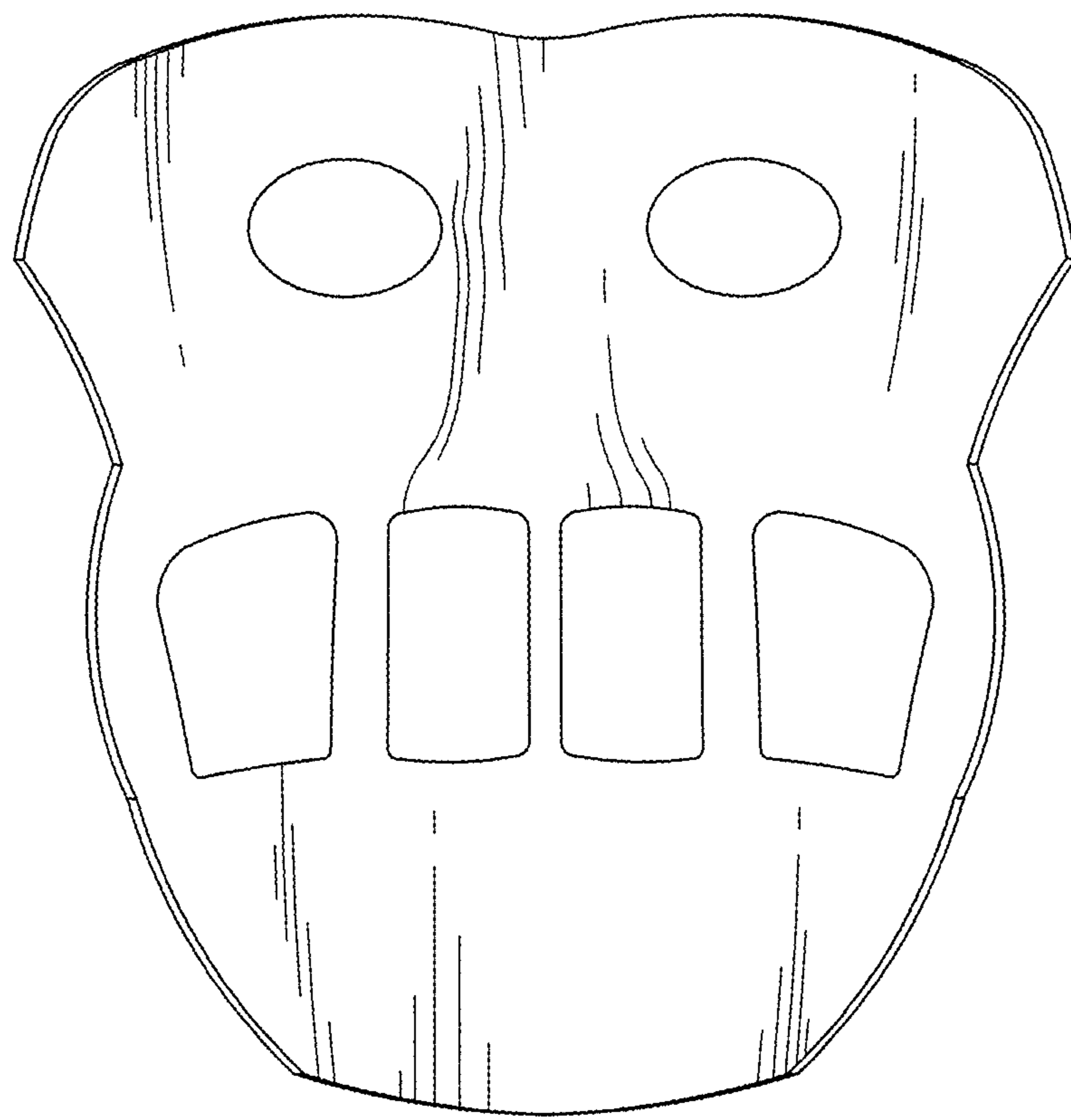


FIG.3

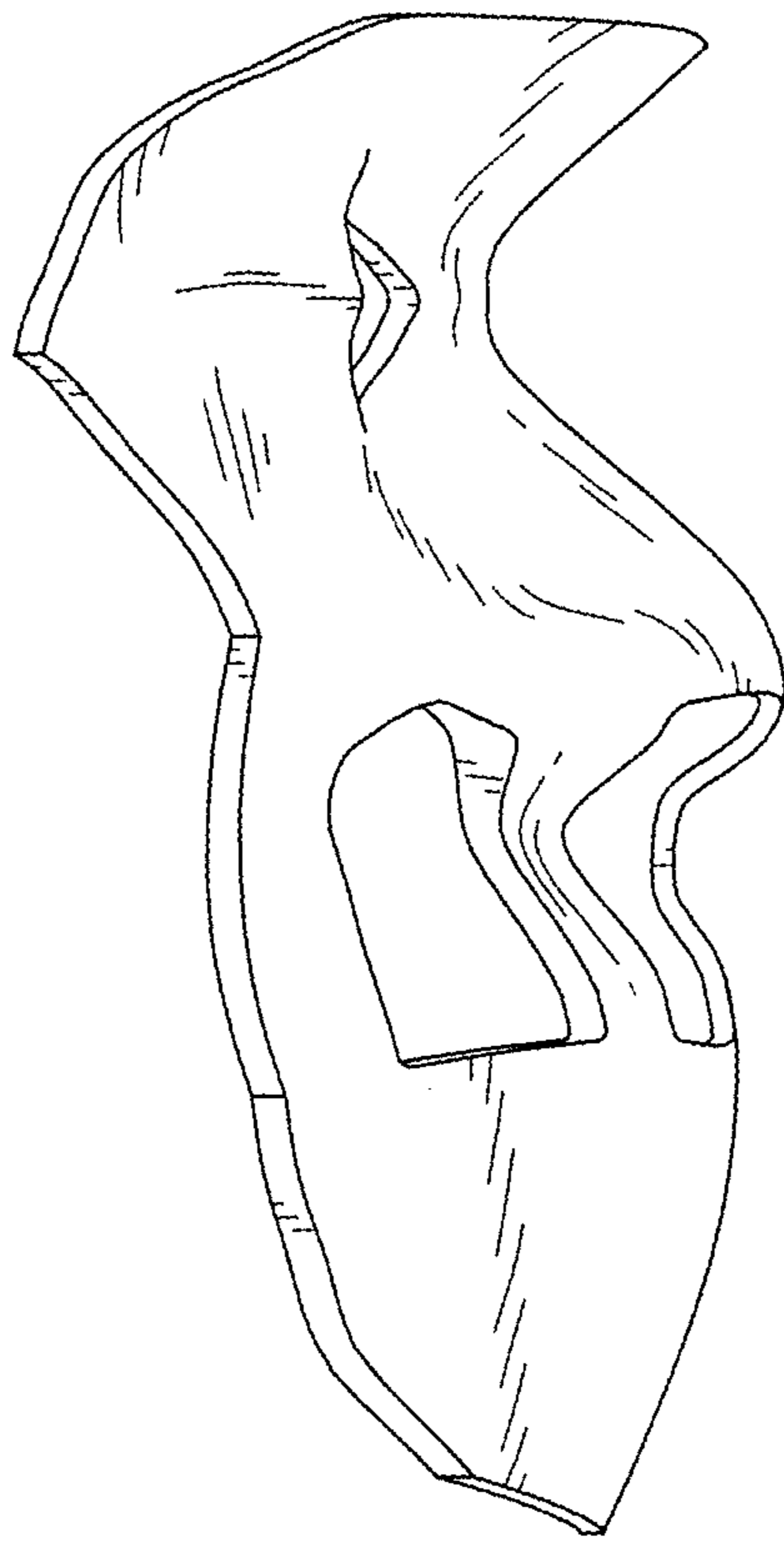


FIG.4

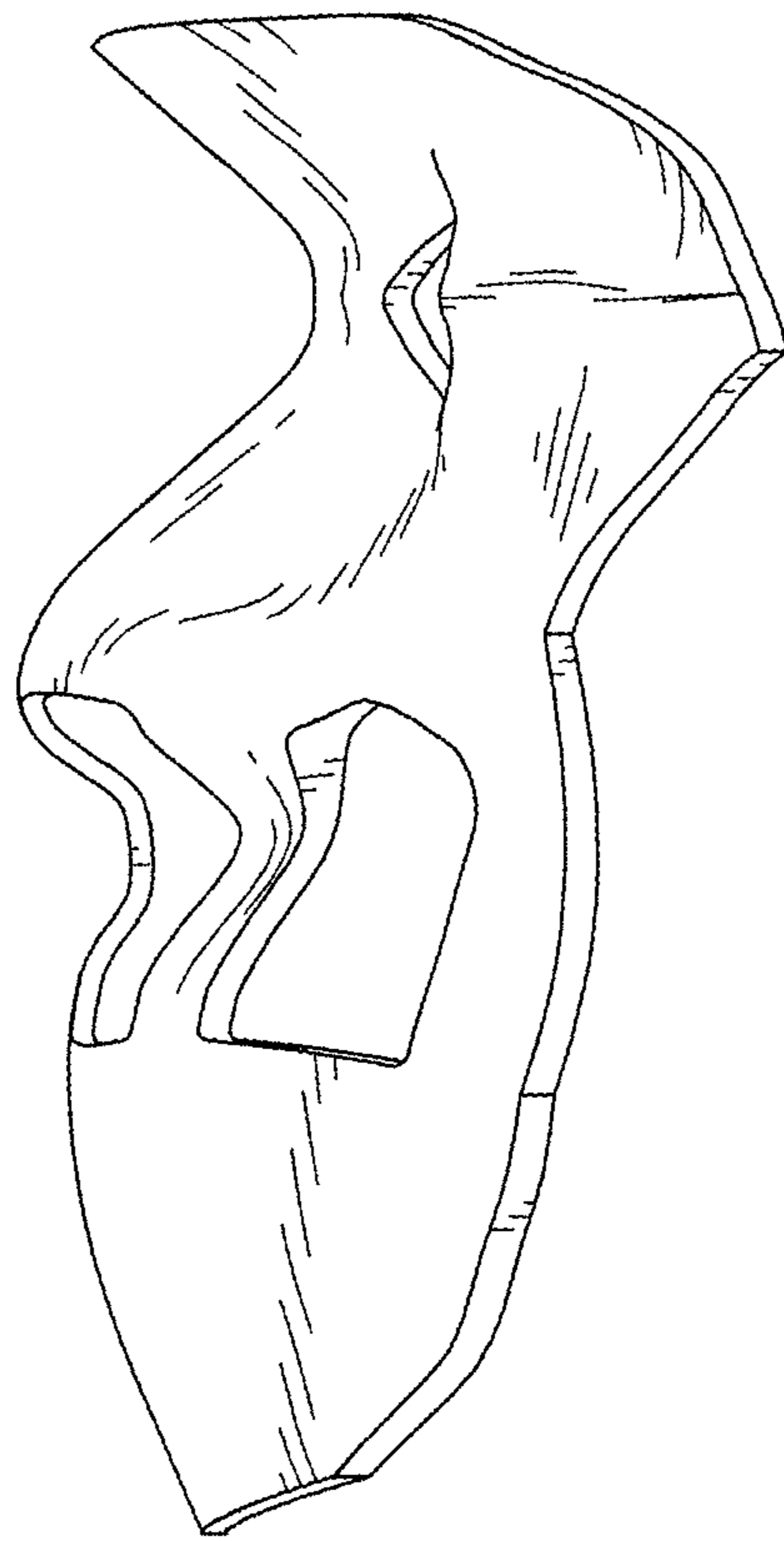


FIG.5

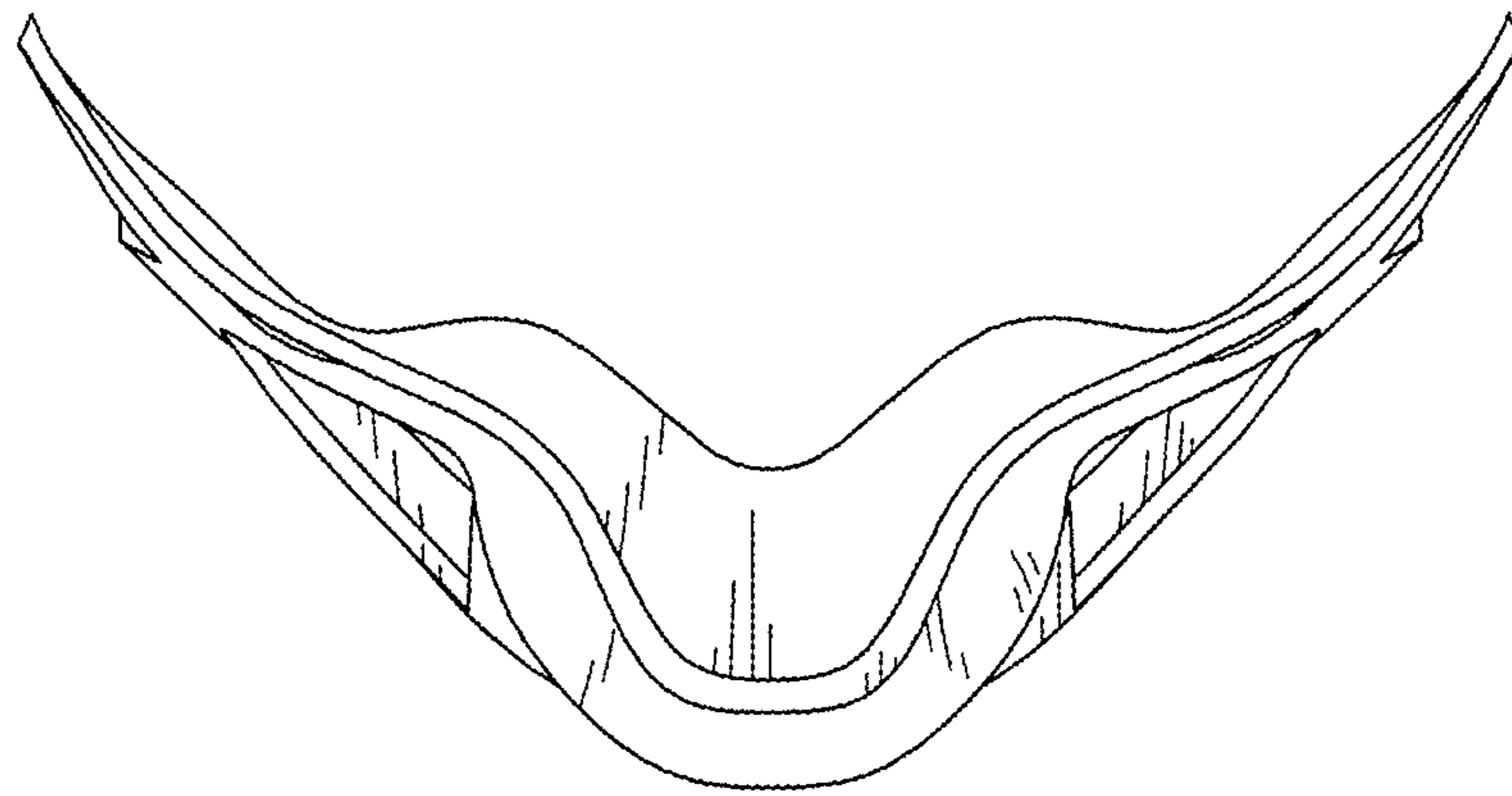


FIG. 6

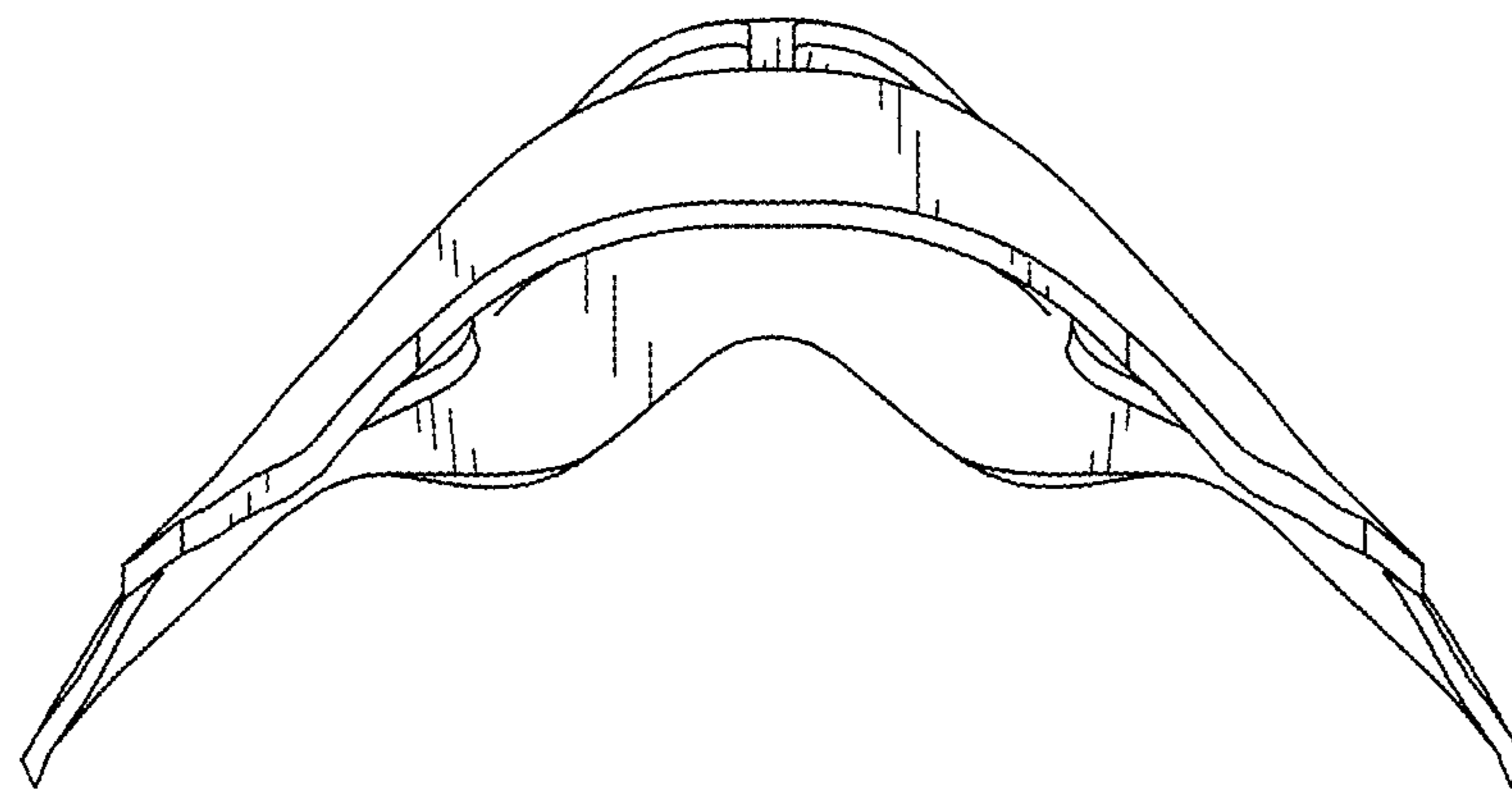


FIG. 7

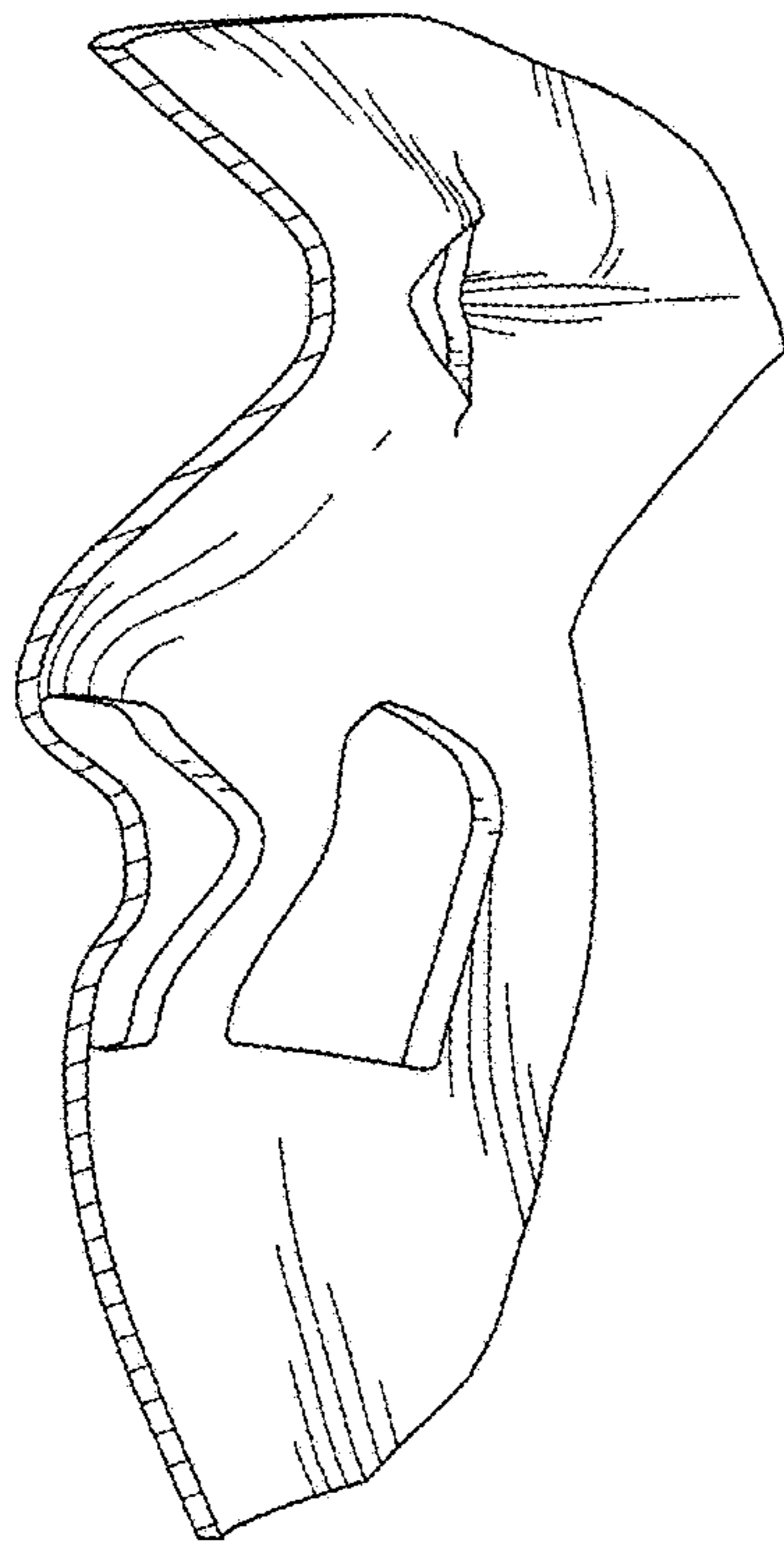


FIG. 8

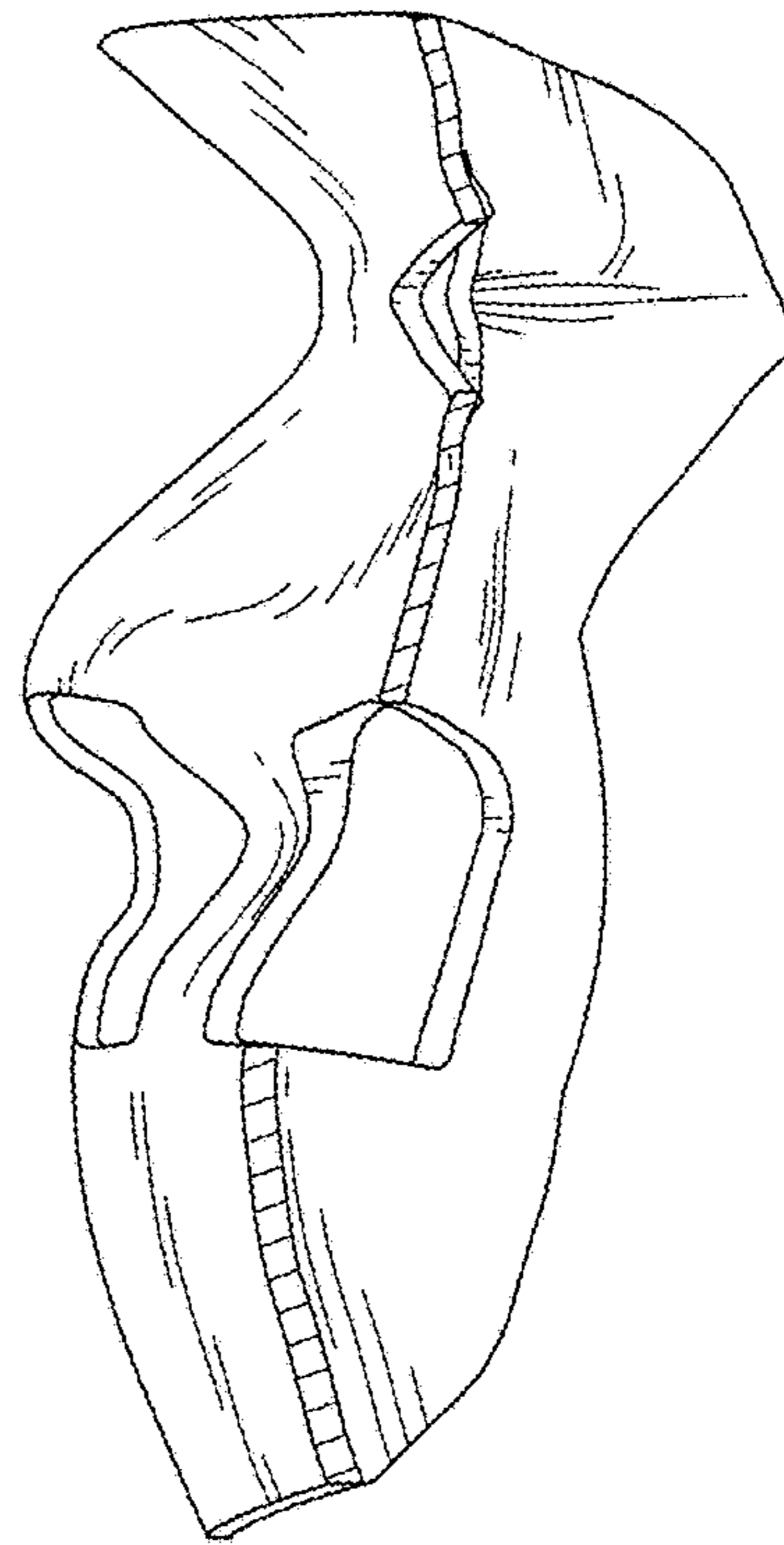


FIG. 9



FIG.10

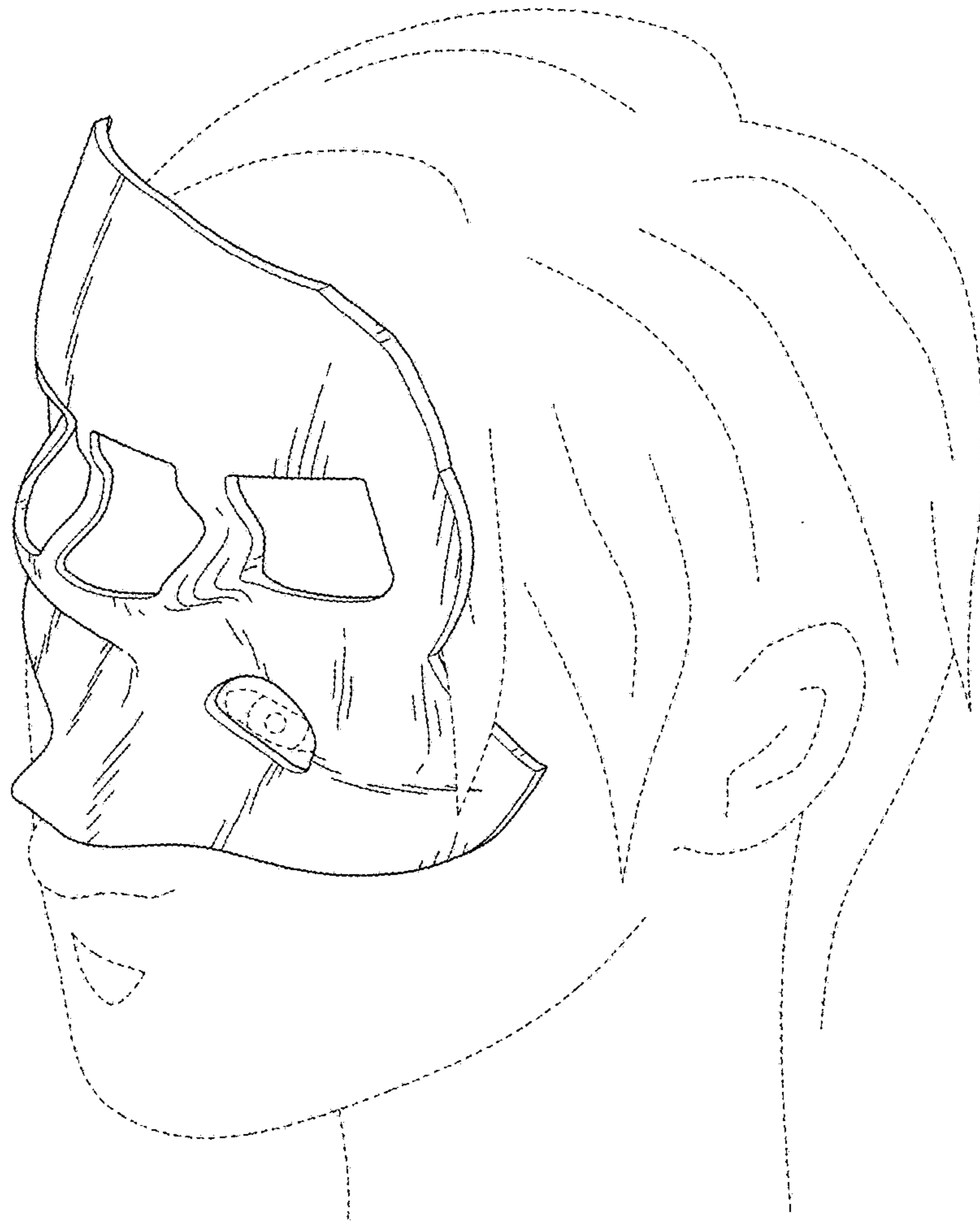


FIG.11